



METROLOGY and TEST beamline

SOLEIL staff:

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Areas of applications, instrumentation and methodologies used

Beamline dedicated to the metrology and characterization of X-ray optical components and detectors. Development of new techniques together with the related instrumentation. Also valuable as a general purpose beamline to prepare, test and set up a wide range of experiments.

METROLOGIE meets the needs of SOLEIL beamlines, Optics Group and Detectors Group, its two partners (CEA-DAM and LNE), the CNRS/Thales-TRT joint research unit and SOLEIL users.

- Source: Bending Magnet.
- Two branches operating simultaneously: Soft X-ray branch [30 to 1800 eV] and hard X-ray branch [100 eV to 40 keV in monochromatic operation mode, with access to the white or pink beam].
- Spectral resolution: 1000 to 10000 depending on the energy range.
- Beam size: from a few hundred microns in focused mode, to several usable millimeters in non-focused mode.
- Flux:

Soft X-ray Branch: 10⁹ to 10¹² photons/s on sample, depending on the energy range.

Hard X-ray Branch: Few 10⁹ photons/s/mm² in monochromatic to 10¹⁴ photons/s/mm² in white

beam operation mode.

- Experimental stations: Two-axis high vacuum goniometer on each beamline branch. Additional equipment on the Hard X-ray branch, including an Optical Table provided with various motorized positioning systems for carrying out experiments at atmospheric pressure, and a deep X-ray photolithography (LIGA) exposure station (CNRS/Thales-TRT).

Major disciplines

- Analysis of the photometric parameters of optical components: surface reflectivity grating and multilayer diffraction efficiency filter transmission.
- Detectors characterization and calibration: photosensitive devices scintillators optical relays.
- Development of optics and diagnostics for X-ray beam spatial and spectral settings.
- Wavefront sensing (Hartmann and Interferometry), Adaptive X-ray Optics, X-ray phase metrology and X-ray phase imaging.
- Primary X-ray source as calibration standard Measurement of Material optical constants (LNE).
- Characterization of X-ray and Plasma Diagnostics to be implemented on the future MegaJoule Laser (CEA-DAM).
- Deep X-ray Photolithography (LIGA).